

Beryllium-based multilayer mirrors for EUV spectral range

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Multilayer mirrors for EUV

Motivation

- Increase the reflection coefficients
- Expand the operation range
- Increase the spectral resolution

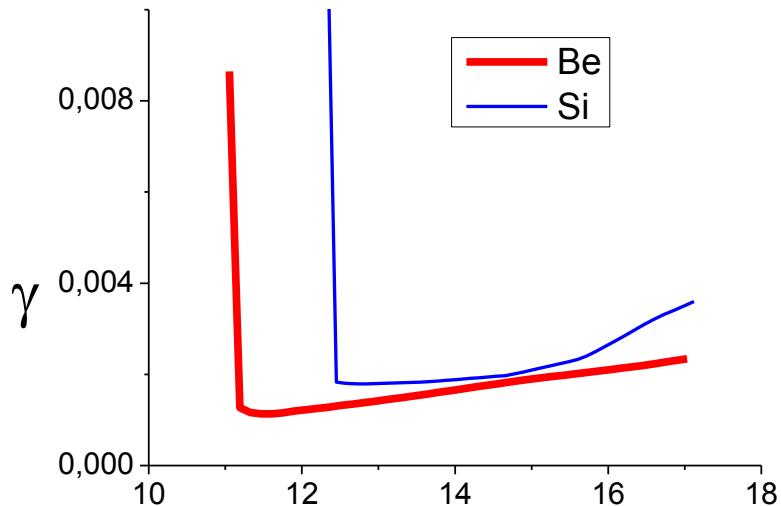
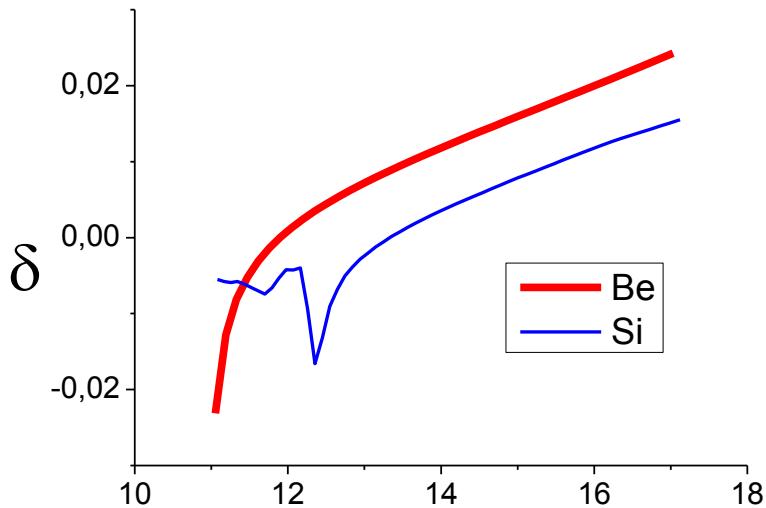
Ways how to solve the problems

- 1. Improving existing approaches:
Barrier layers, ion-assisted and
ion polishing – effect is small!**

- 2. Looking for new materials –
interesting and unpredictable!**

Beryllium as spacer for $\lambda=11\text{-}17$ nm

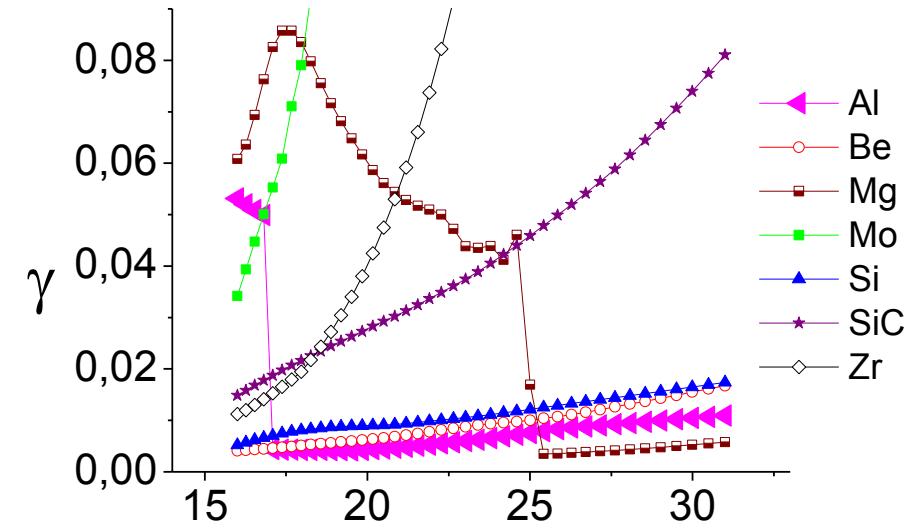
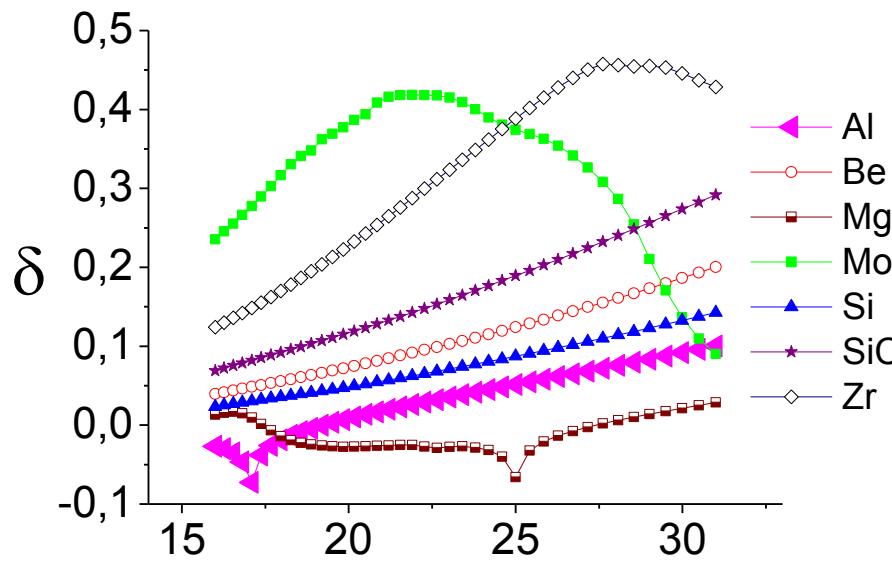
$$\varepsilon = 1 - \delta + i\gamma$$



- No competitors in the range of **11-12.4 nm**
- Smallest absorption in the range of **11-17 nm**

Beryllium as the scattering (contrast) material in 17-30 nm range

$$\varepsilon = 1 - \delta + i\gamma$$



➤ Better than of Si and close to SiC optical contrast and lower absorption make Be as VERY attractive contrast material for EUV range!

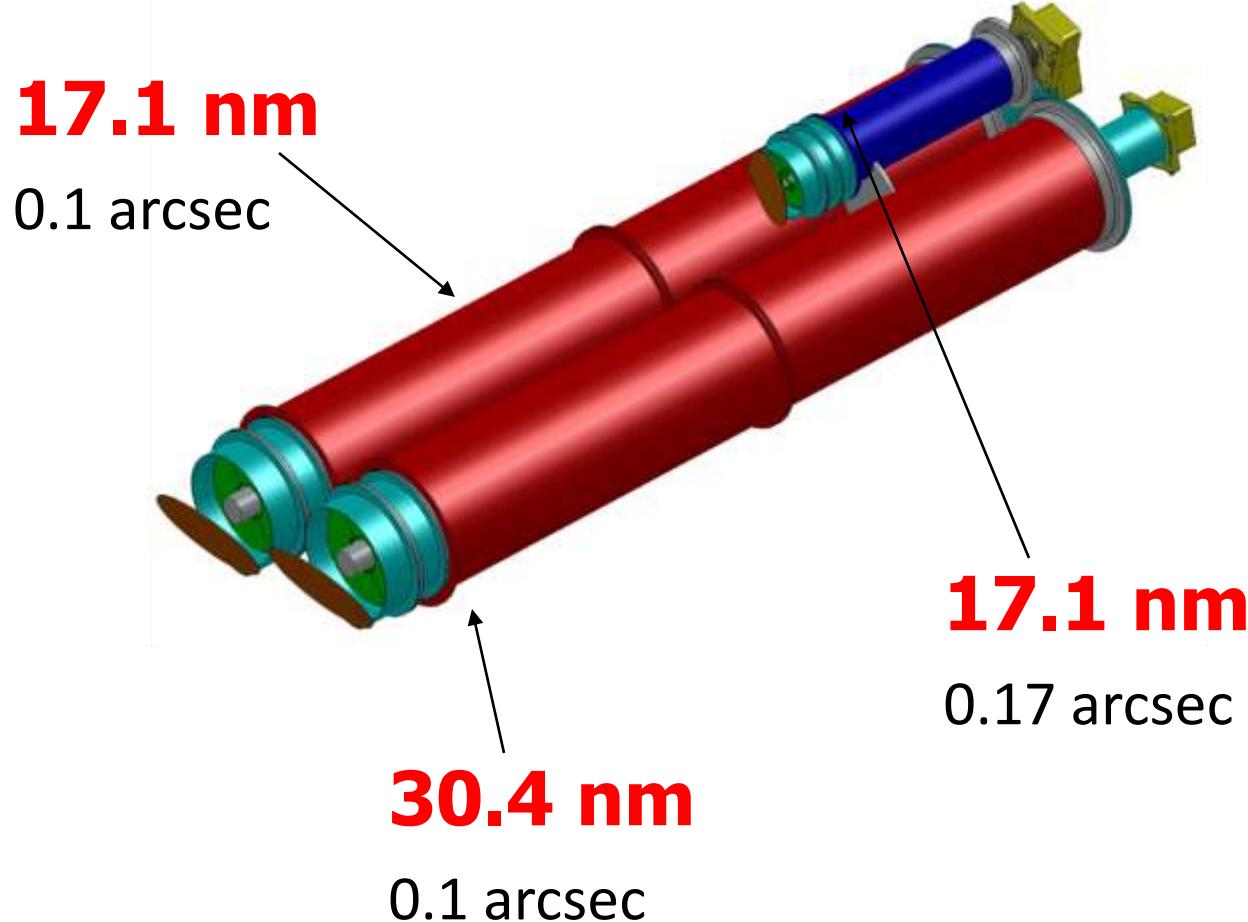
Mirrors for Astrophysics in EUV

Requirements:

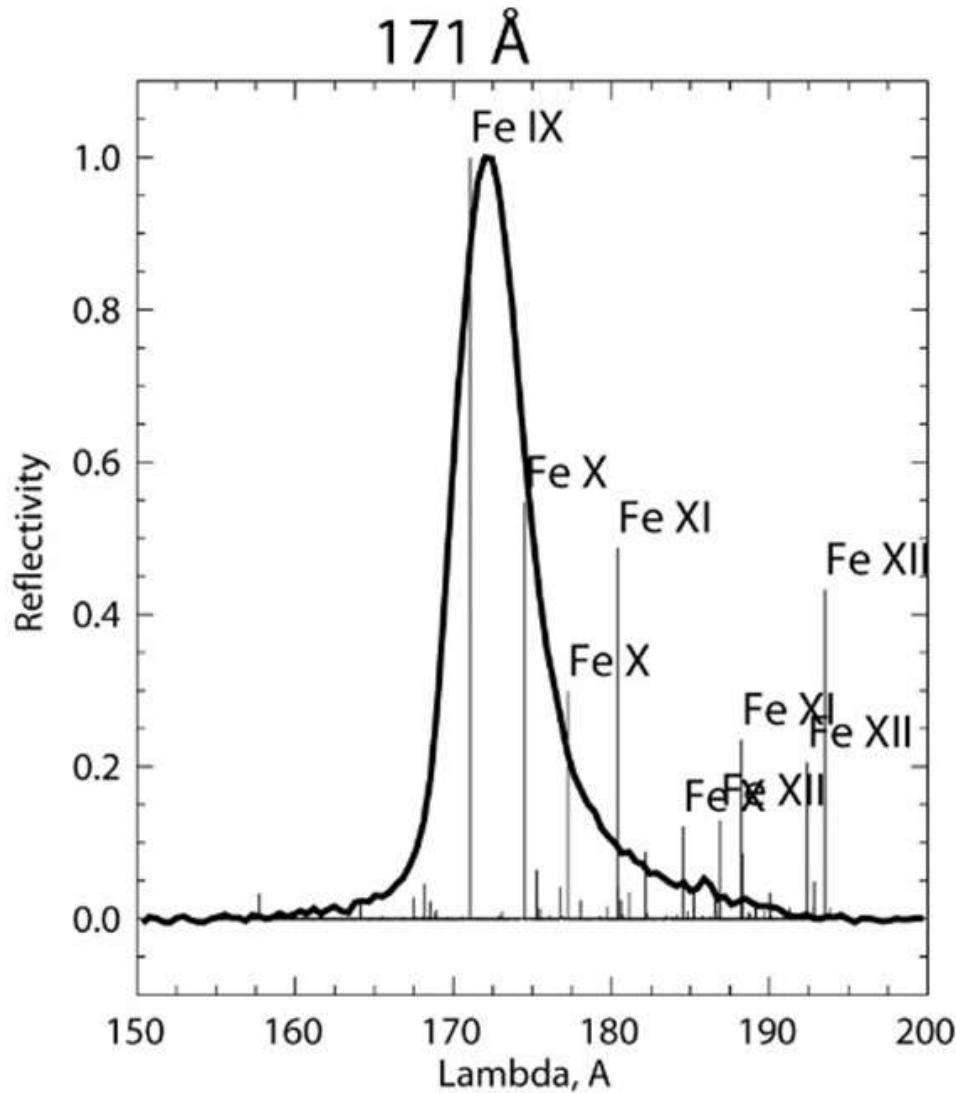
- 1. High reflection coefficients**
- 2. Narrow spectral band-pass**
- 3. Stable operation at least for 5 years**

The ARKA instrumentation

Three Ritchey–Chrétien telescopes



Requirements for $\lambda=17.1$ nm



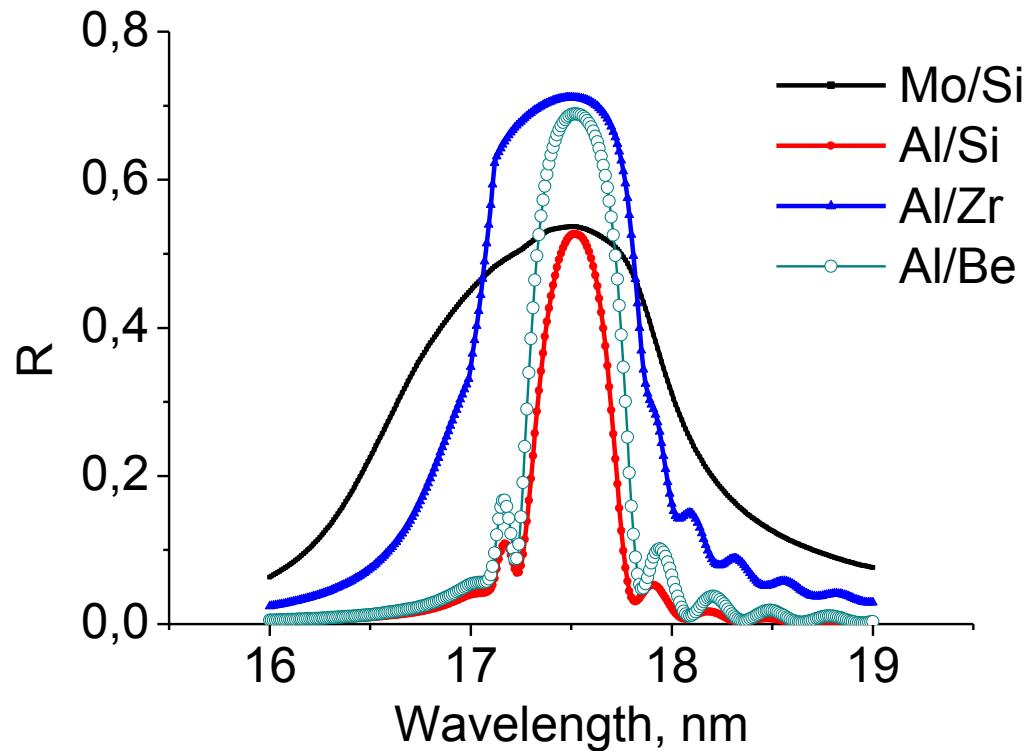
Spectral selectivity:
For single MLM
 $\Delta\lambda < 0.42$ nm
For telescope
 $\Delta\lambda < 0.3$ nm
Rpeak > 45%

Measured characteristics of MLMs at $\lambda=17.1\text{nm}$

Requirements: $\Delta\lambda < 0.42 \text{ nm}$, $R > 45\%$

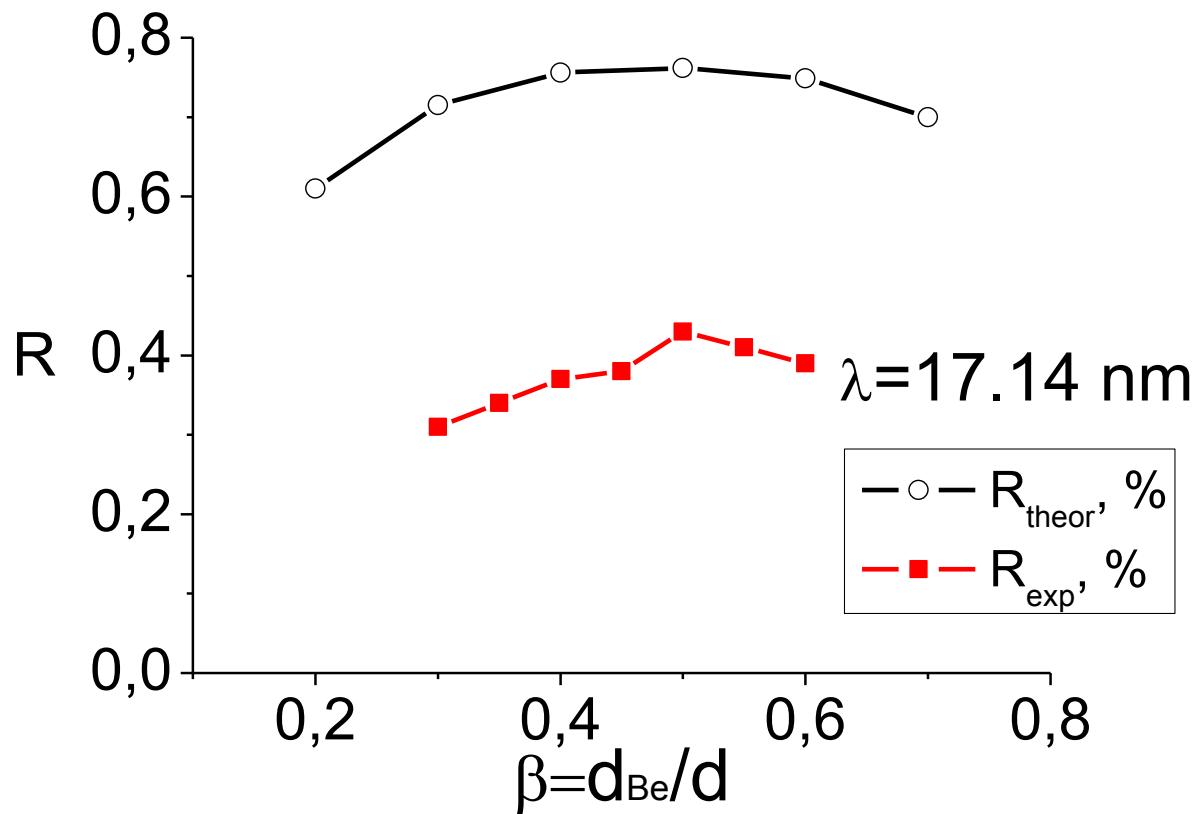
MLMs	R, %	$\Delta\lambda$, nm
Si/Mo₂C	52	1
Al/SiC	38	0.6
Al/Mo/SiC	53.4	0.76
Al/Mo/B₄C	55.5	0.875
Mo/Si	54	0.875
Al/Zr	56	0.6
Al/Si	48	0.35

Calculated reflectivities



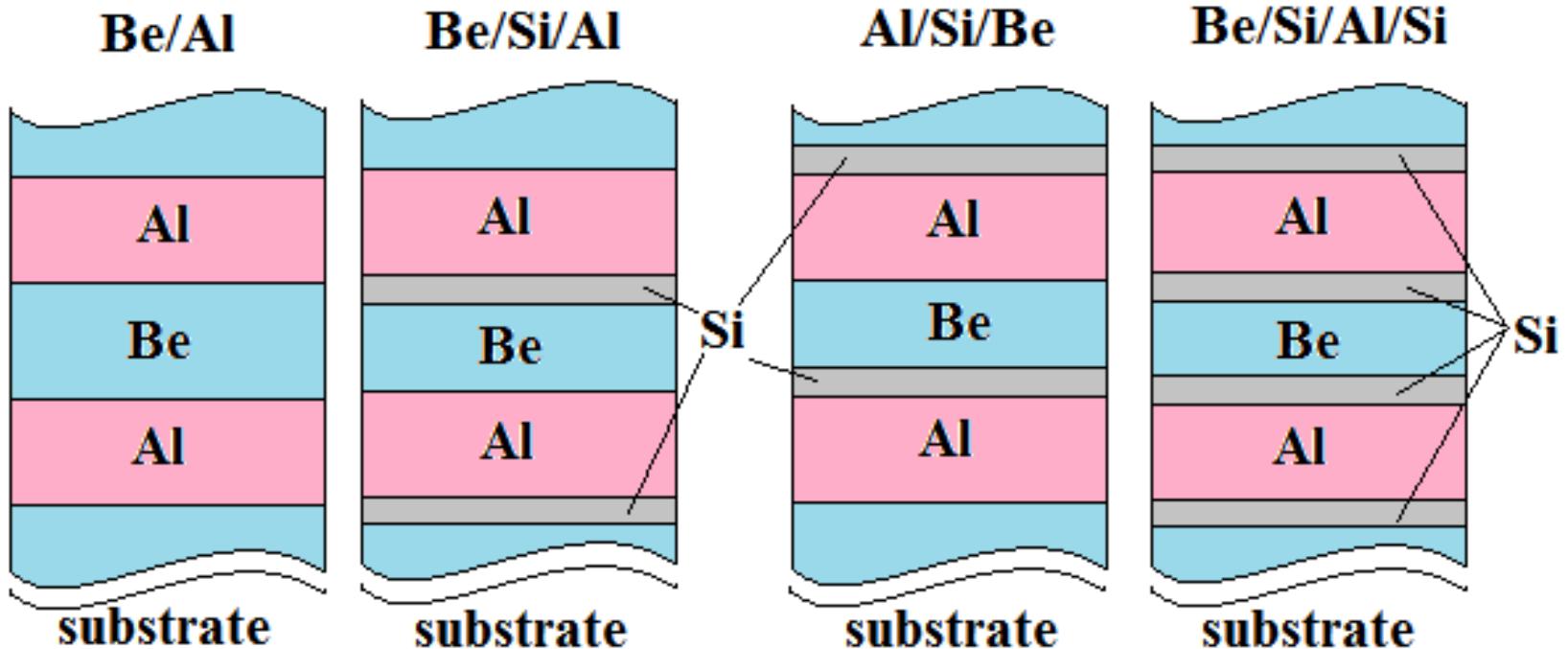
For Al/Be
at $\lambda=17.5$ nm
 $R=69\%$
 $\Delta\lambda=0.45$ nm

Dependences R(β)



Theoretical and experimental dependences of peak reflection coefficients on the proportion of Be in the period

Investigated kinds of MLMs



Comparison of reflectivity

MLMs	R _{theor}	R _{exp}
Be/Al	76.3%	46%
Al/Si/Be	75.3%	51%
Be/Si/Al	73.5%	61%
Be/Si/Al/Si	73.7%	56%

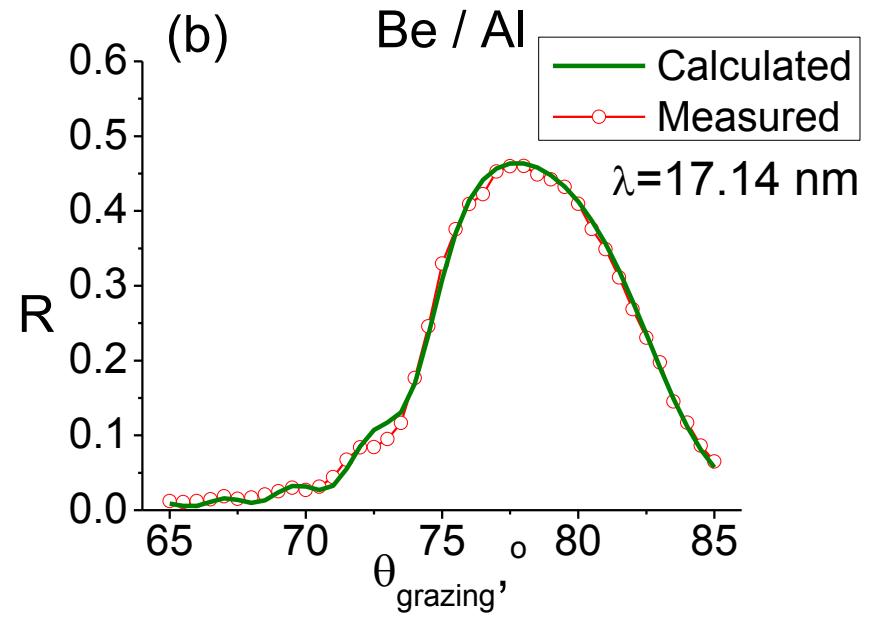
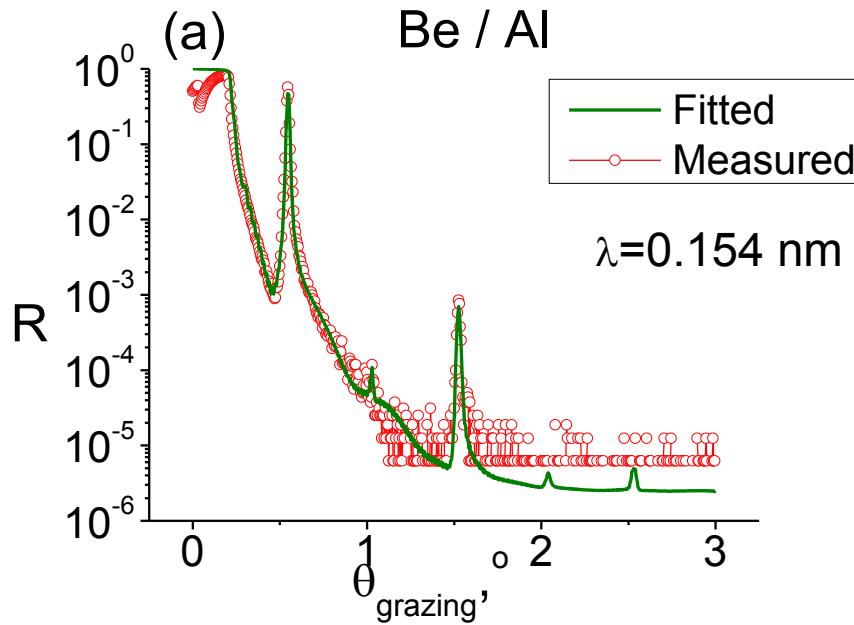
Measured: $\Delta\lambda \sim 0.4$ nm

Measured reflection coefficients of Be/Si/Al

R _{max}	46%	55%	59%	61%	59%	59%	58%
d(Be)	4.8	4.8	4.45	4.25	4.05	3.85	3.65
d(Si)	0.45	0.6	0.8	1	1.2	1.4	1.6
d(Al)	3.65	3.5	3.65	3.65	3.65	3.65	3.65

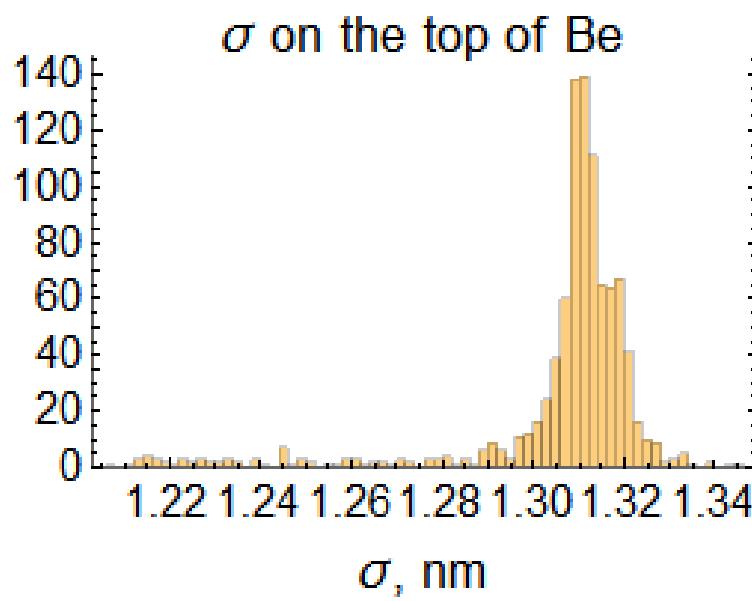
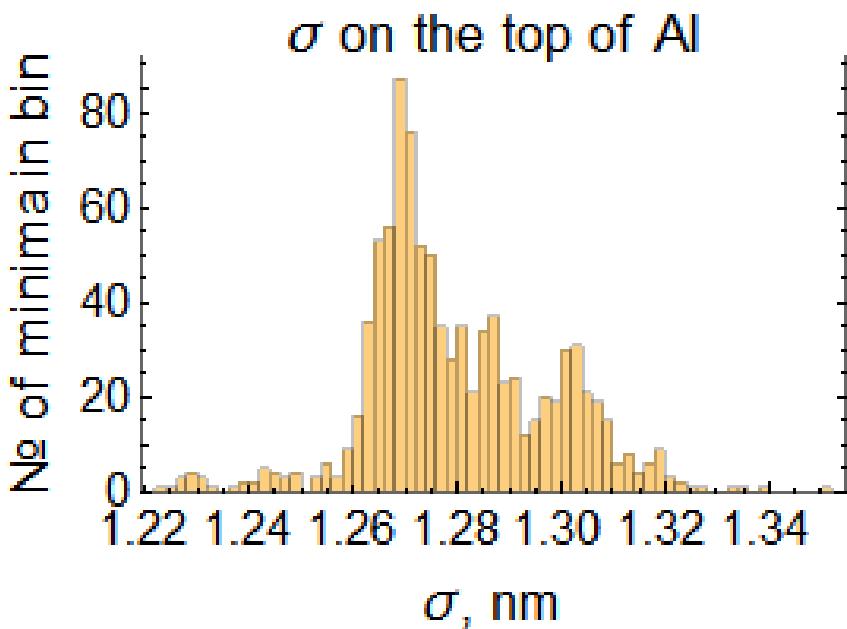
Measured reflection coefficients of Be/Si/Al mirrors with various thicknesses of Be, Si and Al layers at $\lambda=17.14$ nm

Fitting Al/Be



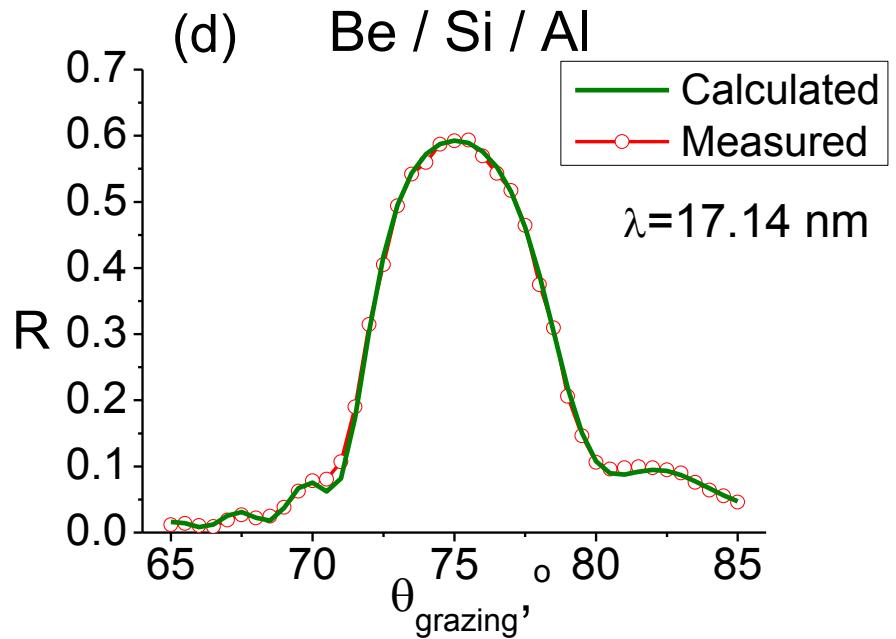
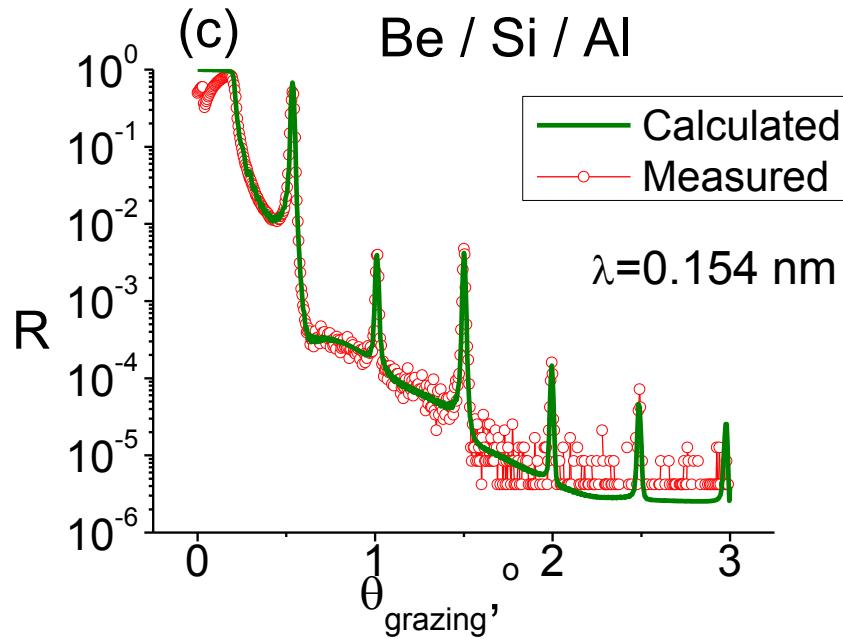
Measured and fitted angular dependencies of the reflectance at $\lambda = 0.154 \text{ nm}$ and $\lambda = 17.14 \text{ nm}$ for the MLM Be/Al.

Interlayer widths Al/Be



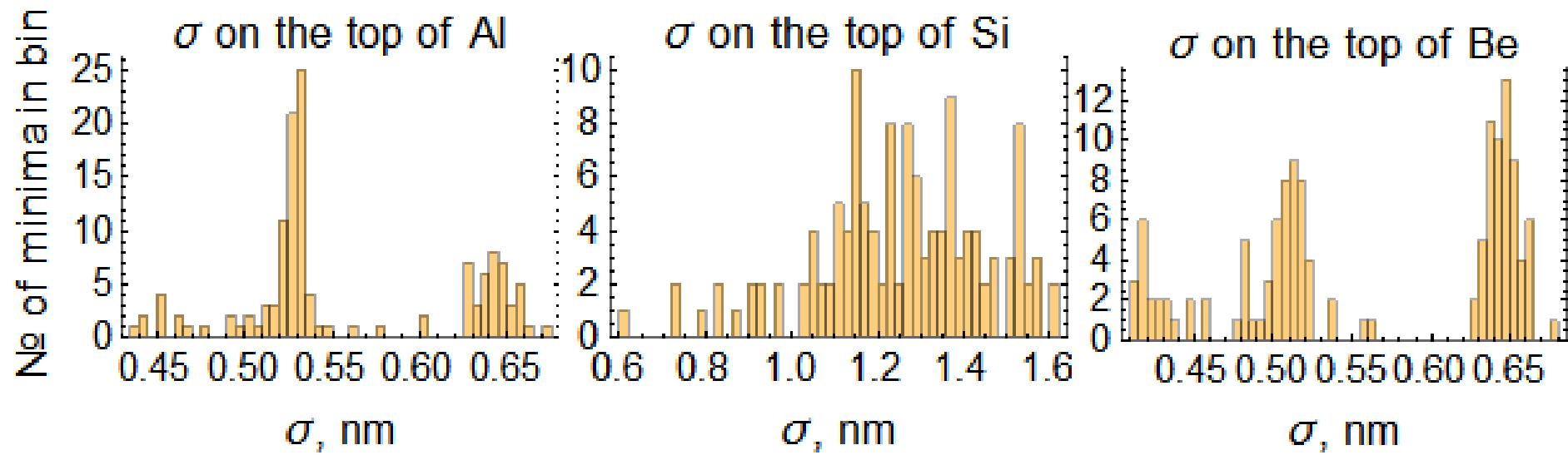
$\sigma_{\text{Be/Al}}(\text{Al}) \approx 1.25\text{--}1.32 \text{ HM}$, $\sigma_{\text{Be/Al}}(\text{Be}) \approx 1.29\text{--}1.33 \text{ HM}$

Fitting Be/Si/Al



Measured and fitted angular dependencies of the reflectance at $\lambda = 0.154 \text{ nm}$ and $\lambda = 17.14 \text{ nm}$ for the MLM Be/Si/Al.

Interlayer widths Be/Si/Al



$\sigma_{\text{Be/Si/Al}}(\text{Al}) \approx 0.5\text{--}0.66 \text{ nm}$, $\sigma_{\text{Be/Si/Al}}(\text{Be}) \approx 0.45\text{--}0.66 \text{ nm}$

Be-based MLSs for 30.4 nm (HeII). Theory and experiment

MLS	R, %	$\Delta\lambda$, nm
Mo/Si	22	~4
Mg/SiC	40 (30)	1.5
Mg/Si	40 (30)	1
Al/Be	27	0.8

Be-based MLSs (theory):

$R(Al/Be) = 46\%$, $\Delta\lambda = 1\text{nm}$

$R(Mg/Be) = 73\%$, $\Delta\lambda = 1.6\text{nm}$

Conclusion

1. We have run certified Be- laboratory for deposition of multilayer mirrors
2. Calculation show that Be-based multilayers are most of interest in spectral ranges of 11-31 nm
3. First experiments demonstrate that in EUV range Be-containing multilayers have better resolution or both better resolution and reflectivity as compared with traditional multilayers

**Thank you very much for your
attention
&
Well come for Collaboration in
Be multilayer optics**

